

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-8 (Canceled)

Claim 9 (New): A processing apparatus for forming a film, comprising:

a chamber;

a gas supply section provided to said chamber for supplying a predetermined gas into said chamber; and

an exhaust opening provided to said chamber so as to face said gas supply section and connected to exhaust means for exhausting an interior of said chamber,

wherein said chamber is structured such that a cross section of a flow passage of said gas, said flow passage going from said gas supply section to said exhaust opening, gradually decreases from said gas supply section to said exhaust opening.

Claim 10 (New): A processing apparatus comprising

a chamber;

a gas supply opening provided to said chamber and connected to gas supply means for alternately supplying plural species of gases into said chamber; and

an exhaust opening provided to said chamber so as to face said gas supply opening and connected to exhaust means for exhausting an interior of said chamber,

said chamber being structured such that a cross section of a flow passage of said gases, said flow passage going from said gas supply opening to said exhaust opening, gradually decreases from said gas supply opening to said exhaust opening.

Claim 11 (New): The processing apparatus according to claim 10,

wherein said chamber is structured such that said cross section of said flow passage of said gases decreases in accordance with a distance from said gas supply opening.

Claim 12 (New): The processing apparatus according to claim 10,
wherein said chamber is structured such that a thickness of a boundary layer is approximately constant, said boundary layer being formed when said gases are supplied into said chamber, on a wall of said chamber that extends along a direction of flow of said gases.

Claim 13 (New): The processing apparatus according to claim 10,
wherein said chamber is structured such that a thickness of a boundary layer is approximately constant, said boundary layer being formed when said gases are supplied into said chamber, on a substrate placed in said chamber approximately parallel with a direction of flow of said gases.

Claim 14 (New): A processing apparatus comprising:
a chamber;
a gas supply opening provided to said chamber and connected to gas supply means for alternately supplying plural species of gases into said chamber; and
an exhaust opening provided to said chamber and connected to exhaust means for exhausting an interior of said chamber,
said chamber having a cross section that has an approximately triangular shape as seen from a direction approximately perpendicular to a direction of supply of said gases, said gas supply opening being provided at substantially an entire one side of said cross section, and said exhaust opening being provided at a vertex portion that faces said one side of said cross section.

Claim 15 (New): A method for processing a substrate placed in a chamber by alternately supplying plural species of gases into said chamber from a gas supply opening and switching atmosphere in said chamber, said method comprising:

supplying a predetermined gas into said chamber from said gas supply opening; and causing said predetermined gas supplied in said gas supplying to flow in said chamber in a manner that said gas has a cross section of flow passage that decreases in accordance with a distance from said gas supply opening.

Claim 16 (New): The processing method according to claim 15, wherein in said gas flow, a boundary layer having an approximately constant thickness is formed on a wall of at least one of said chamber and said substrate, along a direction of flow of said gas.

Claim 17 (New): The processing apparatus according to claim 9, wherein said gas supply section includes a plurality of gas supply holes arranged approximately parallel with a direction of width of said chamber.

Claim 18 (New): The processing apparatus according to claim 17, wherein said gas supply section includes a gas diffusion section connected to said gas supply holes.

Claim 19 (New): The processing apparatus according to claim 9, wherein said cross section of said flow passage is formed so as to be in reverse proportion to a distance from said gas supply section.

Claim 20 (New): The processing apparatus according to claim 19,
wherein said cross section of said flow passage is formed by a width of said chamber that is approximately constant and a height of said chamber that decreases along a direction of flow of said gas.

Claim 21 (New): The processing apparatus according to claim 9,
wherein a boundary layer having an approximately constant thickness is formed on a inner wall of said chamber along a direction of flow of said gas.